Accepted Manuscript

Effects of acetylene flow rate and processing temperature on graphene films grown by thermal chemical vapor deposition

Chih-Sheng Chen, Chien-Kuo Hsieh

PII: S0040-6090(14)01269-3 DOI: doi: 10.1016/j.tsf.2014.12.012

Reference: TSF 33974

To appear in: Thin Solid Films



Please cite this article as: Chih-Sheng Chen, Chien-Kuo Hsieh, Effects of acetylene flow rate and processing temperature on graphene films grown by thermal chemical vapor deposition, *Thin Solid Films* (2014), doi: 10.1016/j.tsf.2014.12.012

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.

ACCEPTED MANUSCRIPT

Effects of acetylene flow rate and processing temperature on graphene films grown by thermal chemical vapor deposition

Chih-Sheng Chen and Chien-Kuo Hsieh*

Department of Materials Engineering, Ming Chi University of Technology,

New Taipei City 24301, Taiwan

*Corresponding author. Tel.:+886 2 2908 9899x4438; fax: +886 2 2908 4091.

E-mail address: jack_hsieh@mail.mcut.edu.tw (C.-K. Hsieh)

Download English Version:

https://daneshyari.com/en/article/1664862

Download Persian Version:

https://daneshyari.com/article/1664862

<u>Daneshyari.com</u>